**K-series approximation of vectorial optical fields for designing diffractive optical elements with subwavelength feature sizes**

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**Abstract:** Diffractive optical elements (DOEs) are widely applied as compact solutions for desired light manipulations via wavefront shaping. Recent advanced chip applications further require their feature sizes to move down to the subwavelength, which inevitably brings forth vectorial effects of optical fields and makes the typical scalar-based theory invalid. However, simulating and optimizing its vectorial fields, which are associated with the billions of pixel parameters in the optical element, are difficult to do, because of the issues on numerical stability and the highly-demanding computational cost. To address this problem, this research proposes an applicable algorithm by means of wave-vector (k) series approximation of vectorial optical fields. Together with the semi-analytical rigorous coupled wave analysis (RCWA), an adequate selection scheme on k-series enables computationally efficient yet still predictive calculations for DOEs. The performance evaluations for exemplary designs by the finite difference time domain (FDTD) method show that the predicted intensity profiles by the proposed algorithm agree with the target by a fractional error. Together with optimizing the degrees of freedom (i.e. DOE depth h) as compensation for errors from the cut of k-series, the algorithm demonstrates its outperformance by one or two orders of magnitude in accuracy versus the scalar-based model, and demands only a reasonable computational resource under a specific selection of k-series.

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1. **Introduction**

Diffractive optical elements (DOEs) are devices composed of transparent materials with complex topography to realize specified functions (e.g. optical computing and cell trapping [1, 2]) that are not feasible with standard refractive optics. With the rapid development of additive manufacturing techniques [3–5] in recent years, especially two-photon polymerization lithography (TPL) [6–8], it has become more feasible to fabricate DOEs with feature sizes down to ten nanometers. Thus, the technology is widely used for optical applications in the visible band, such as holograms for virtual reality [9], colorful 3D prints [10], and optical anticounterfeiting devices [11]. Moreover, TPL has been proven to bear potential at producing DOEs for advanced chip-scale applications like all-optical diffractive deep neural networks [12–14]. However, in this feature size regime, the assumptions of typical scalar-based design methods are violated [15, 16] and the vectorial effects of optical fields become pronounced [17]. A general, fully rigorous design tool is therefore needed to enable an accurate synthesis of such elements. So far this is quite a challenging work for researchers.

A small amount of literature has reported on designing DOEs with subwavelength feature sizes. For DOEs in the 1D domain, D.W. Prather et al proposed an optimization-based algorithm using the boundary element method (BEM) [18]. Its computational costs, however, prevent the design of realistic DOEs in reasonable time frames. J. Jiang et al. developed the microgenetic algorithm FDTD method [19], but it remains a challenging practical design tool due to its time-consuming searching routines. M.E. Testorf et al. demonstrated the Gerchberg-
Saxton-algorithm FDTD method [20], which is a highly efficient optimization algorithm, but is related to the paraxial design algorithm. Feng Di et al. employed an iterative optimization algorithm [21, 22] based on the rigorous electromagnetic theory for a 1D beam splitter, which is still subject to time-consuming and local-searching-only issues. In the 2D domain, H. Hao et al. presented a hybrid method that combines the rigorous coupled wave analysis (RCWA) [23] and the genetic algorithm [24] to design 2D wide-angle beam splitters. The method, however, precludes designs from DOE’s applications other than splitters. Thus, it is an urgent requirement to develop an efficient algorithm for designs of DOEs that are finite in extent (mm- to cm-scale), have subwavelength features, and are aperiodic for different functions.

On the back of the scalar-based simulated annealing algorithm (s-SAA) [25], this research proposes a vector-based simulated annealing algorithm (v-SAA) for designing DOEs with subwavelength feature sizes. Considering the vectorial effects of optical fields dominantly taking place inside the elements, this work mainly re-models the wave front function $U(x_D, y_D)$ of DOEs in s-SAA with the rigorous electromagnetic theory. Here, the wave vectors $k$ are further discretized and categorized in terms of vector orientations and sampling rates, so that v-SAA can perform computationally efficient yet still predictive calculations according to an adequate selection of terms in $k$-series.

The rest of the paper runs as follows. Section 2 describes the detailed design algorithm. Section 3 presents the design results and analysis to demonstrate the effectiveness of v-SAA. Section 4 concludes this work.

2. Design principle

2.1. Limits of the scalar-based theory

To interpret the deviation from prediction by the scalar-based theory in systems with subwavelength feature size, in this paragraph we employ the rigorous electromagnetic theory to accurately investigate vectorial optical fields. First, one exemplary DOE is introduced to discuss vectorial effects by a comparison between the scalar-based theory and FDTD method. The studied binary $5 \times 5$ DOE is composed of square pixels having feature size $\Lambda_{ph}$ and depth $h$, as in Fig.1(c). In which two kinds of materials, the substrate medium with refractive index $n_2 = 1.5$ and the air with $n_1 = 1.0$, occupy the pink and transparent grids, respectively. Figure 1(a) illustrates the transmission fields on the exiting surface of DOE (at $z=h=\lambda$) by FDTD, provided a plane-wave incidence with wavelength $\lambda$ and structure parameter $\Lambda_{ph}/\lambda = 6$. In this refractive-optics regime-i.e., $\Lambda_{ph}/\lambda \gg 1$ - the numerical results show that the intensity of optical fields is dependent on the individual morphology of a pixel, is approximately uniform, and has almost constant amplitude value $|E| = 1$. In Fig.1(a'), the phase of the fields is distinctly associated with pixel morphology, and the value of the phase difference between two kinds of pixels is $\pi$, confirming the predication by the scalar-based theory [25]. Compared to Fig.1(a), Fig.1(b) demonstrates the transmission fields in DOE having subwavelength feature size $\Lambda_{ph}/\lambda = 0.6$. Figures 1(b) and 1(b') clearly present that not only the intensity but also the phase of the optical fields signify the mechanism of pixel-pixel couplings, and reveal the sub-profile of fields inside a single pixel. The assumption of uniformity and single-pixel-dependence of optical fields made by the scalar-based theory is hence considerably invalid. Moreover, the results seem to imply that the single-value representation of optical fields per pixel can be problematic in the regime $\Lambda_{ph}/\lambda \leq 1$.

To explore the generality of vectorial effects for systems studied, we statistically analyze fields of the central pixel in DOE as a function of pixel size, using an ensemble of 20000 specimens per $\Lambda_{ph}$ value. Similar to the schematic DOE in Fig. 1(c), each specimen has its plane dimension $3.5\lambda \times 3.5\lambda$ and is provided with stochastic pixel morphology except for the central measure pixel. Here, the FDTD method is adopted for giving convincing conclusions. Numerical results for amplitudes of different field components on exiting surface ($z=h=\lambda$) are plotted in Fig. 2(a), provided the incident field has x polarization. The phase curve of the field’s x component is
shown in Fig. 2(b), while the curves for the other two components are not displayed owing to their simple uniformly random distribution over the 0-2π range. In fact, Fig. 2 portrays the properties of optical fields from the regime Λ/λ ≫ 1 belonging to the scalar-based theory (ST), across the regime Λ/λ ≤ 1 belonging to vectorial optics, and to the regime Λ/λ ≪ 1 belonging to the effective medium theory (EMT) [16]. Indeed, numerical results show that the amplitude and phase of fields exhibit asymptotic convergence toward constants E_{x,EMT} and φ_{E_{x,EMT}} by EMT at Λ/λ ≪ 1, and toward constants E_{x,ST} and φ_{E_{x,ST}} by ST at Λ/λ ≫ 1, respectively. Considerable depolarization and dephasing of fields, however, occur in the in-between regime and hence demand vector-based theories for different requirements.

Fig. 2. (a) Normalized amplitude of different field components and (b) phase of the field’s x-component at the central pixel as a function of pixel size by ensemble statistics. The FDTD method is adopted here for valid conclusions.
2.2. Selection scheme of k-series to compute pixel fields by vectorial model

For vectorial effects, Figs. 1(b)-(b’) show that the optical fields of DOE with $\Lambda_{ph}/\lambda = 0.6$ display across-pixel continuity and a sub-pixel profile. These observations imply that the local field can couple with that of distant pixels during propagation in DOE, and its profile presents sub-pixel variations. Thus, without loss of generality, in this work the fields in DOEs are expressed as a Fourier expansion in terms of the spatial harmonics [23], and the series are approximated by considering two mechanisms: the coupling class $r$ and the sampling rate $s$. In Fig. 3(a) the coupling class $r$ defines the maximal pixel range of pixel-pixel couplings by $(\Lambda_{eff}/\Lambda_{ph} - 1)/2$, where the size of an equivalent-isolated pixel $\Lambda_{eff}$ should be infinite in theory for accuracy but is set as a finite value by assuming insignificant interactions of fields among remote pixels.

The proposed method hence requires only a finite morphology of nearby pixels within $\Lambda_{eff}$ to determine the local field within $\Lambda_{ph}$, but still can keep predictive calculations. In Fig. 3(b), the sampling rate $s$ defines the number of sampling points per pixel for one dimension, in order to help describe an accurate sub-pixel profile of fields and enable occurrences of higher-order diffractions. Herein, we assume that overly wide-angle (high-order) diffraction fields are away from desired functions and hence excessively fine profiles can be more than necessary. Thus, with an adequate setup of $r$ and $s$ values, this work fulfills more accurate and efficient vectorial modeling of near fields in DOEs, in place of the typical wave front function in the scalar-based theory. In RCWA, this $(r,s)$ selection scheme demands the most-dominant $s\times\Lambda_{eff}/\Lambda_{ph}$ of wave vectors series for a single dimension, in which the orientation scope and the discretization spacing of wave vectors are order of $\Lambda_{ph}/s$ and $1/\Lambda_{eff}$, respectively.

Fig. 3. (a) Schematic definition for coupling class $r=(\Lambda_{eff}/\Lambda_{ph} - 1)/2$ of fields in unit of pixel by $r=1$, and (b) schematic definition for sampling rate $s$ per pixel by $s=3$.

To investigate the validity of the proposed scheme, we re-evaluate the same analysis in Fig. 2 by the proposed vectorial modeling, and compare results with those in Fig. 2. Figure 4(a) allows us to evaluate the average amplitude of different field components at the central pixel on the exiting surface by RCWA ($r=s=2$). Figure 4(b) plots the curve for the corresponding phase of x fields. Curves by FDTD are signified by dotted lines for comparison. The asymptotic constant values based on EMT and ST methods are denoted as horizontal dotted lines near the belonging regimes in the figure. Analyses with low $(r,s)$ values in Fig. 4 display qualitatively similar variations of fields to that by FDTD as varying $\Lambda_{ph}$. Numerical results using values $r=s=4$ are shown in Fig. 5, which portray quantitatively similar curves to that by FDTD, and clearly predict more accurate vectorial effects (e.g. depolarization and dephasing of fields) for systems studied. We conclude that, instead of the simplified wave front function in the scalar-based theory, the proposed scheme enables a flexible set-up for vectorial effects so as to realize efficient yet predictive computations.

2.3. Vector-based simulated annealing algorithm

This work considers a Fourier-transformed DOE, where the coordinates of the image plane are denoted $(x_1,y_1)$ and those of the exiting plane on DOE are denoted $(x_{D,s},y_{D,s})$. DOE is assumed
Fig. 4. (a) Normalized amplitude of different field components and (b) phase of the field’s x-component at the central pixel as a function of pixel size by ensemble statistics. Solid curves indicate results by RCWA (r=s=2), and dotted curves show those by FDTD for comparison.

Fig. 5. (a) Normalized amplitude of different field components and (b) phase of the field’s x-component at the central pixel as a function of pixel size by ensemble statistics. Solid curves indicate results by RCWA (r=s=4), and dotted curves show those by FDTD for comparison.
to be illuminated by a plane wave. The reconstructed image is derived in the focal plane of the Fourier lens.

According to the pixel morphology of DOE, the fields \( P(x_{D,s}, y_{D,s}) \) for each pixel \((x_D, y_D)\) are fast computed by the k-series approximation model, where the subscript \( s \) represents the index of sampling points per pixel. The reconstructed profile \( R \) of DOE is given by

\[
R(x_I, y_I) \subset F\left[P(x_{D,s}, y_{D,s})\right]^{-1} = \sum_{x_{D,y_D}=-N/2}^{N/2} \sum_{s=1}^{N^2} P(x_{D,s}, y_{D,s}) e^{2\pi i \left(\frac{x_{D,s}}{N} x_I + \frac{y_{D,s}}{N} y_I\right)}
\]

Here, \( F^{-1} \) is the inverse Fourier transform, DOE is an optical element of \( N^2 \) square pixels, and the pixel field \( P \) is an \((N \times s) \times (N \times s)\) array function. In practical operation \( x_I \) and \( y_I \) are selected as the lowest \( N^2 \)-order wave vectors of a total \((N \times s)^2\) ones, responding to an \( N^2 \)-pixel target image \( I_0 \). The intensity \( I \) of the reconstructed profile is given by:

\[
I(x_I, y_I) = |R(x_I, y_I)|^2
\]

The merit function to score performance of reconstruction is defined as the mean-square error between the reconstructed image and the desired images \( I_0 \), presented by:

\[
m = \int \int |I_0(x_I, y_I) - \alpha I(x_I, y_I)|^2 \, dx_I \, dy_I
\]

Here, \( \alpha \) is a scale factor given by:

\[
\alpha = \frac{\int \int I_0(x_I, y_I) \, dx_I \, dy_I}{\int \int I(x_I, y_I) \, dx_I \, dy_I}
\]

Here, the merit function is obviously zero when the reconstructed image equals the desired image.

The algorithm is performed by the following steps.

1. The pixel morphology of DOE is initially obtained according to the discretization of phase distribution of the Fourier transform of an desired image. The temperature parameter of the simulated annealing \( T_0 \) is initially set at a relatively high value, enabling a large range of the perturbation probability.

2. One pixel \((x_{Dr}, y_{Dr})\) of DOE is randomly selected for perturbation. The pixel morphology (or depth) is reset by a random candidate of depth levels. The pixel fields \( P(x_{Dr,s}, y_{Dr,s}) \) are then updated by the k-series approximation model, where the nearby reference pixels are assumed to follow periodic arrangement for simplification.

3. The difference of merit function \( \Delta m = m_{\text{new}} - m_{\text{now}} \) is then calculated. If \( \Delta m \) is negative, then the new pixel morphology is accepted; otherwise, acceptance or rejection is determined by the Boltzmann probability:

\[
\Theta(\Delta m) = e^{-\frac{\Delta m}{T}}
\]

4. Repeat steps 2 and 3 for all the pixels of DOE and the annealing cycle, where \( T \) is made lower with the number of annealing cycles by

\[
T = \frac{T_0}{1 + n}
\]

A faster Fourier-transform algorithm is proposed in [25] for large-extent DOEs. A Matlab code for the first-order algorithm \((r=1\) and \( s=1 \)) is available in MATLAB Central File Exchange [26].
2.4. Two-stage optimization process

To achieve high-quality DOEs, we introduce another optimization of the degrees of freedom (i.e. DOE depth $h$) to compensate for deviations of optical fields. In principle, for systems with subwavelength scale in this work, field errors are primarily attributed to two issues: vectorial effects and approximation by the termination of k-series. Thus, a two-stage optimization process is proposed in this work to deal with these two issues. Moreover, we employ a scaled-down sample of the desired product as a temporary prototype during the two-stage process to enable fast computations. As indicated in Fig. 2, the vectorial optical fields within the subwavelength region noticeably depart from the prediction by the scalar-based theory. For this reason, in the first optimization stage, with varying $h$ values, different DOE masks are separately generated by means of the vector-based theory, and the highest-quality one DOE$_{d,vSAA}$, as well as its design depth $h_d$, is determined. Considering the k-series approximation, however, the intensity and phase of optical fields by v-SAA are distinct from those by FDTD, as seen in Figs. 4 and 5. The design depth $h_d$ in theory hence can be inconsistent with the depth $h_p$ for products. To determine the optimal $h_p$ value, in the second stage, the performance of the given mask DOE$_{d,vSAA}$ is directly scored by FDTD under varying set-ups of depth. Owing to the usage of the scaled-down prototype and the single-time optical computation per $h$, the second stage only demands a low computational cost. Consequently, with given parameters in the two-stage process, the full DOE mask can be designed by v-SAA, using depth value $h_p$. The DOE produce is manufactured with an alternative set-up of depth $h_p$ for optimal device performances. The specific processes will be described in detail in the next section.

3. Design results and analysis

To evaluate the feasibility of the proposed algorithm, a beam shaper (i.e. the inset mesh in Fig. 7(c)) is adopted as the desired pattern. The simulation condition is set by the plane-wave incidence, the wavelength $\lambda = 1.0 \mu m$, the incident angle $\theta = 0^\circ$, TM polarization, the refractive index of air $n_1 = 1.0$, the refractive index of DOE material $n_2 = 1.5$, the square-pixel size $A = 0.6 \mu m$, the default depth $h_{def} = 1.0 \mu m$ by s-SAA, the coupling class $r=1$, and the sampling rate $s=1$ position per pixel, for designing a 201$\times$201 pixel array of binary DOEs. The 3D schematic of DOEs is shown in Fig. 1(c). The full structure of DOEs is represented by an image matrix, as Figs. 7(a) and 8(a), where the cyan area indicates the material medium ($n_2$) and the blue area is the air-filling region ($n_1$).

Before generating the full 201$\times$201 design, a temporary 101$\times$101 DOE is employed for speeding up the two-stage optimization process, so as to quickly determine the optimal design depth $h_d$ and product depth $h_p$. At the first stage, with varying depth parameter $h$, a different DOE mask is separately generated, and its intensity of zero-order diffraction is recorded for quality score. As for the numerical analysis in Fig. 6(a), the optimal design depths are $h_{d,sSAA} = \lambda$ and $h_{d,vSAA} = 1.05 \lambda$, corresponding to their generated binary masks DOE$_{d,sSAA}$ and DOE$_{d,vSAA}$ by s-SAA and v-SAA models, respectively. At the second stage, with given candidates DOE$_{d,sSAA}$ and DOE$_{d,vSAA}$, the zero-order intensities at different product depths are directly evaluated by FDTD to determine more a precise depth parameter for manufacturers. Figure 6(b) shows that the optimal product depths are $h_{p,sSAA} = h_{p,vSAA} = 1.15 \lambda$ for this case. In Fig. 6(b) the large zero-order intensity signifies the low-quality DOEs that are designed by the s-SAA model at a subwavelength feature scale.

With determined parameters in the two-stage process, the full 201$\times$201 DOE mask can be designed by SAA using the set-up of depth $h_d$. The DOE product thus is manufactured at an alternative set-up of depth $h_p$ for optimal device performances. Figure 7(a) illustrates the mask of binary DOE designed by the s-SAA model using $h_d = 1.0 \lambda$. The 4-threads optimization computation executes 100 iterations, which converges the variation of the merit function below 0.01% per iteration, in 160.9 seconds. The 201$\times$201 DOE mask designed by the v-SAA($r=1,s=1$)
Fig. 6. (a) The intensity of zero-order diffraction corresponding to different DOEs that are separately designed with varying $h/\lambda$, using s-SAA and v-SAA models, respectively, and (b) Revaluations of zero-order intensity as a function of $h/\lambda$ for candidate DOE in (a) by means of FDTD, which determines the final optimal product depth for s-SAA and v-SAA models, respectively.

model using $h_d = 1.05\lambda$ is depicted in Fig. 8(a). Similarly, the 4-threads optimization calculation executes 100 iterations in 1336.9 seconds, plus an additional computation time of 1.4 seconds for building a $L^{(2r+1)^2} s^2$-size lookup table here ($L=2$ for binary DOEs). To evaluate the validity of the designs, with given $h_p = 1.15\lambda$, the reconstructed images of DOEs are directly simulated by means of well-known softwares [27, 28] that use the rigorous electromagnetic theory FDTD. Figure 7(b) shows the reconstructed image that corresponds to DOE in Fig. 7(a), and its height plot in lower resolution is shown in Fig. 7(b'). The target pattern is put as an inset mesh in Fig. 7(b') for comparison. Here, rather than the typical intensity image $I = |E|^2$, the reconstructed image is presented by the amplitude value of fields $|E|$ for clarity purpose. The 4-threads FDTD program executes the single-time optical propagation of DOE in 23389.1 seconds, in comparison with 1.6 seconds by s-SAA and 13.4 seconds by v-SAA. Numerical results indicate that the DOE designed by the s-SAA model under the subwavelength feature scale exhibits low diffraction efficiencies, owing to the big zero-order spot. The numerical results for DOE by v-SAA are portrayed in Fig. 8. The corresponding reconstructed images are illustrated in Fig. 8(b) and 8(b'). Accordingly, we find that diffraction efficiencies can be clearly enhanced by adopting the vector-based v-SAA model, where the zero-order intensity is suppressed. Thus, this DOE demonstrates a reconstructed pattern closer to theoretical designs. Moreover, the DOEs presented only serve as a straightforward illustration for the proposed approach. Beyond these binary DOEs, arbitrary designs with finite device extent and complex surface morphology could also be generated based on the model and methods.

4. Conclusion

This study has described in detail a vector-based optimization tool for designing DOEs with subwavelength feature sizes. By introducing an adequate selection scheme of k-series, the algorithm can perform computationally efficient yet with predictive computations. Together with an optimization of additional degree of freedom (i.e. DOE depth h) as compensation for errors from the termination of k-series, this work presents DOEs with diffraction efficiencies close to the theoretical limit. Furthermore, after implementing with lookup table techniques to pre-calculate pixel fields under ergodic couplings with nearby ones, the vector-based algorithm can achieve large-extent (mm- to cm-scale) designs in time frames comparable to those of
Fig. 7. (a) The mask of binary DOE designed by s-SAA, (b) the reconstructed image, and (b’) its height plot in lower resolution.

Fig. 8. (a) The mask of binary DOE designed by v-SAA \((r=1, s=1)\), (b) the reconstructed image, and (b’) its height plot in lower resolution.

scalar-based models.

References


